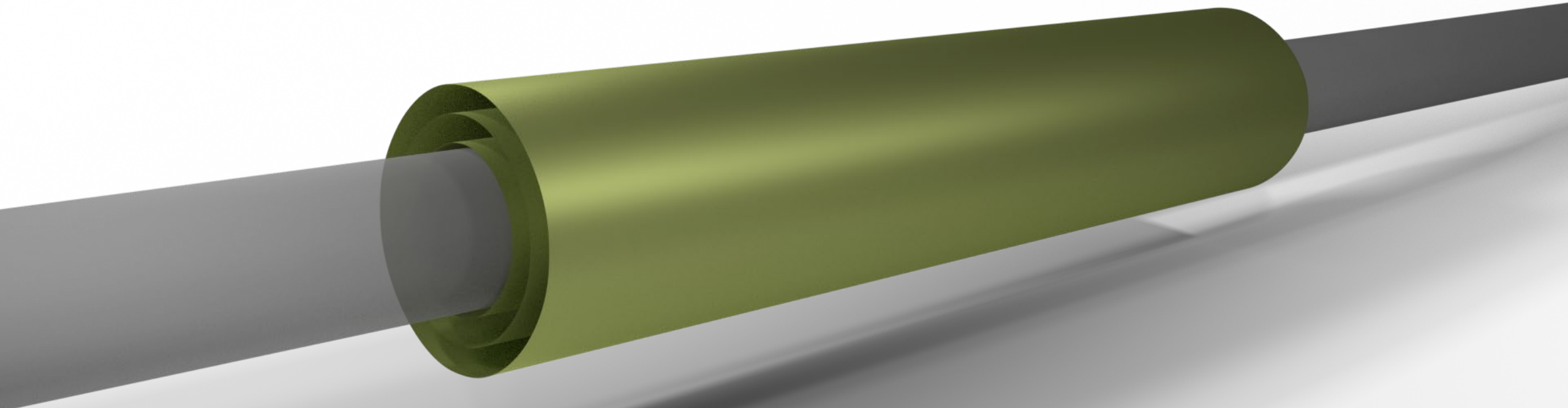


The ALICE ITS3 Project: progress report

Giacomo Contin

Università di Trieste and INFN Sezione di Trieste

on behalf of the ALICE ITS3 Project



- The ITS3 Project
- Detector motivations and layout
- Progress report on main R&D topics:
 - Sensor development (see Iain's talk later)
 - Thinning, Bending, Interconnections
 - Bent chip tests
 - Mechanics

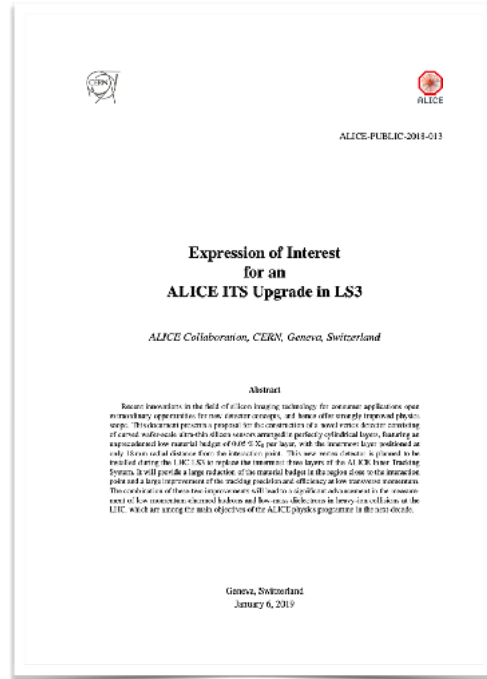
ITS3 Project formation

EoI (2018-2019)

LoI (Sep 2019)

LHCC 139 (Sep 2019)

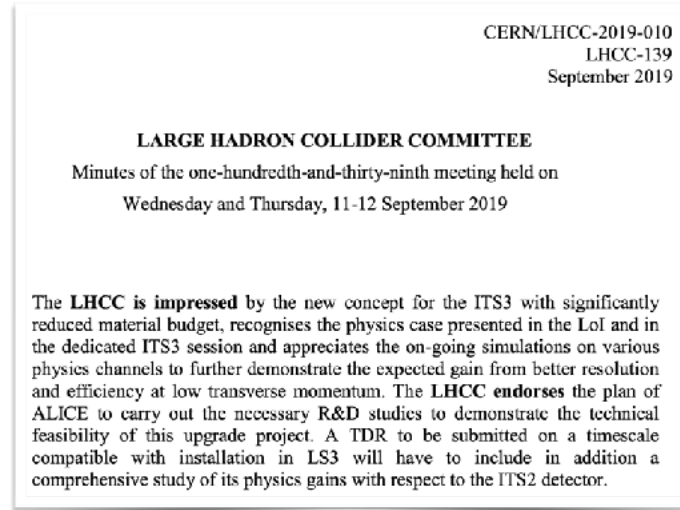
LHCC 142 (Jun 2020)



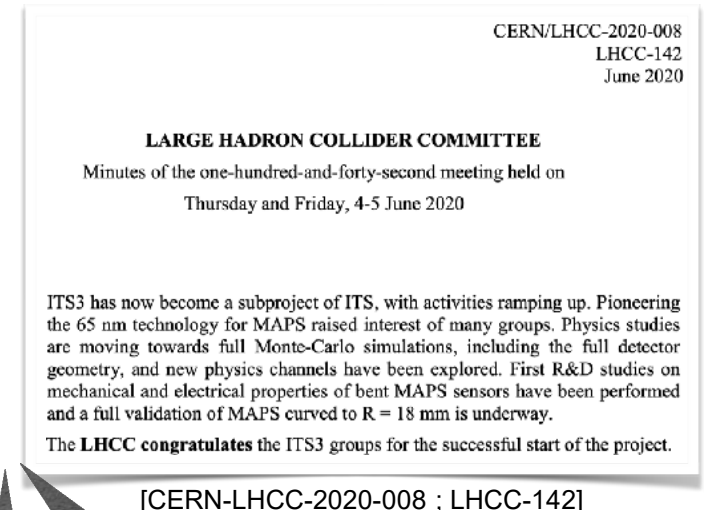
[ALICE-PUBLIC-2018-013]
<https://cds.cern.ch/record/2644611>



[CERN-LHCC-2019-018 ; LHCC-I-034]
<https://cds.cern.ch/record/2703140/>



[CERN-LHCC-2019-010 ; LHCC-139]
<https://cds.cern.ch/record/2689443>



[CERN-LHCC-2020-008 ; LHCC-142]
<https://cds.cern.ch/record/2719880>

R&D kick-off (Dec 2019)



[<https://indico.cern.ch/e/its3-kickoff>]

Project set-up (spring 2020)

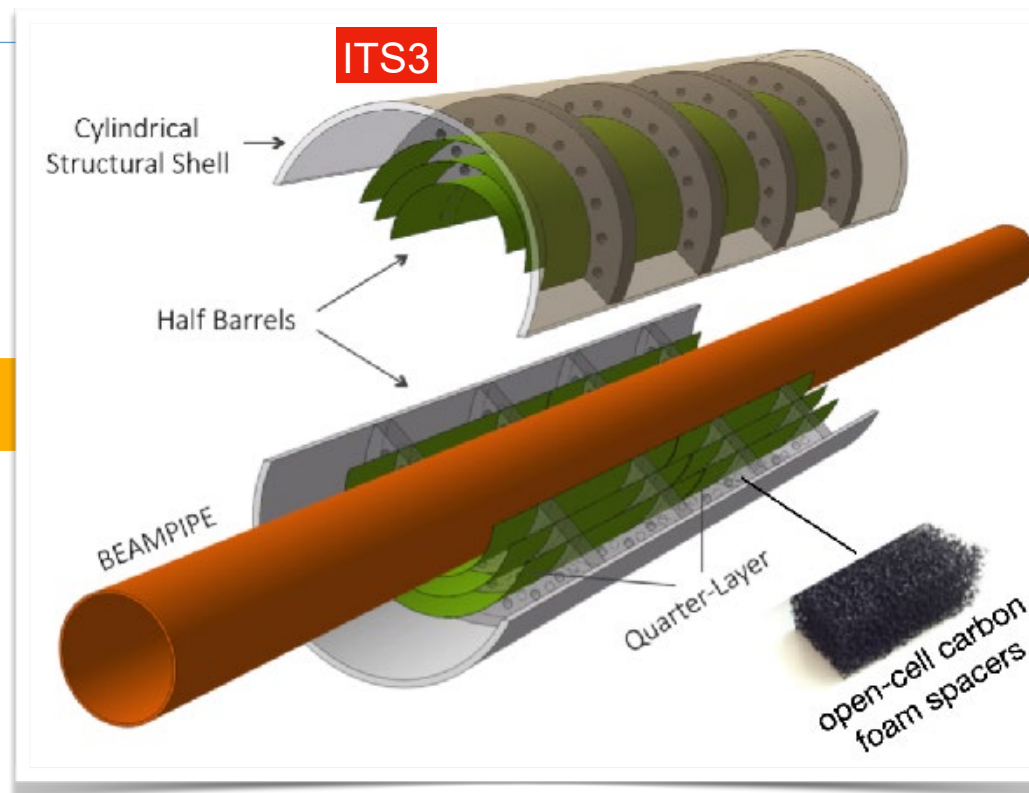
- Project leaders
- Work packages conveners
- Discussion with institutes to participate (ongoing)

ITS3 detector layout

replace



by



in LS3

key improvements:

- ▶ closer to beam pipe: 23→18 mm
- ▶ less material: 0.3 → ~0.03 % X_0

main benefit:

- ▶ better tracking performance
- ▶ especially at low p_T

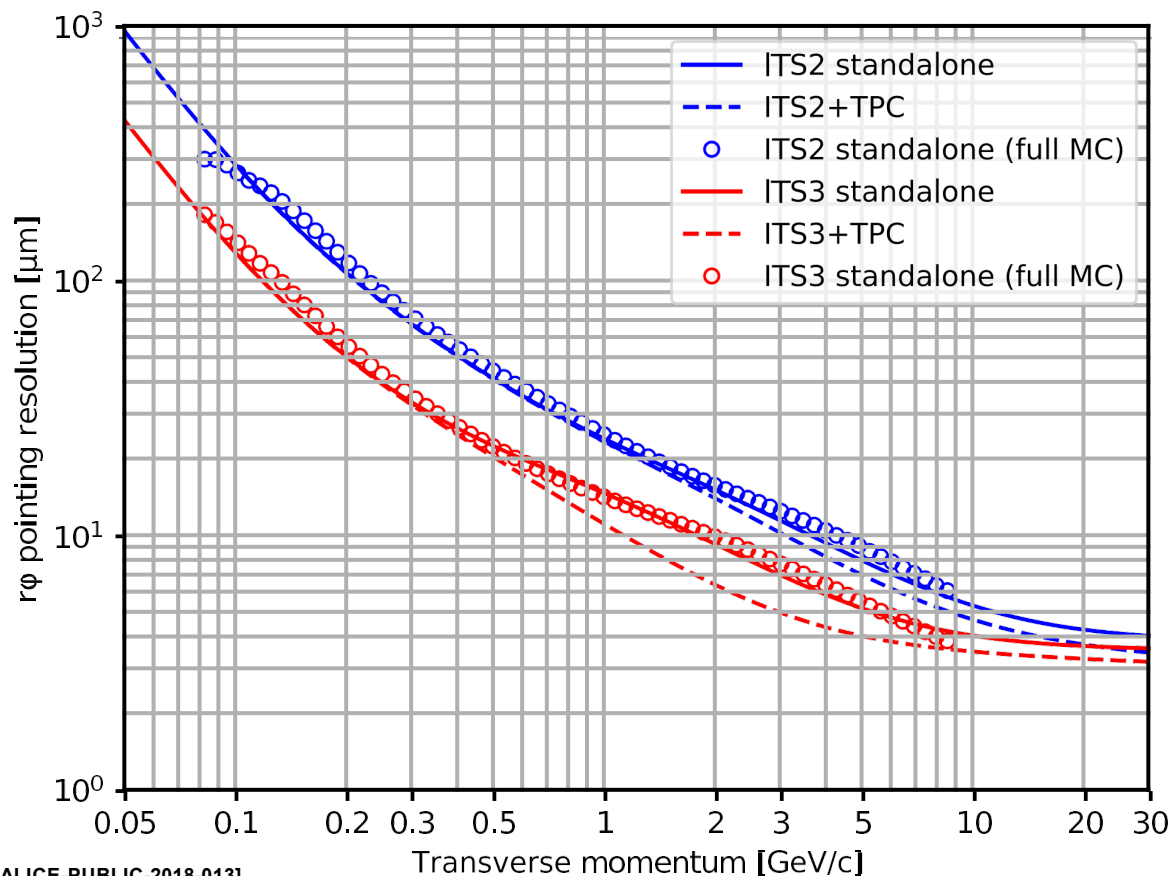
based on:

- ▶ wafer-scale (up to ~28x10 cm),
- ▶ ultra-thin (20-40 μm),
- ▶ bent ($R=18, 24, 30$ mm)

Si sensors (MAPS)

ITS3 projected performance

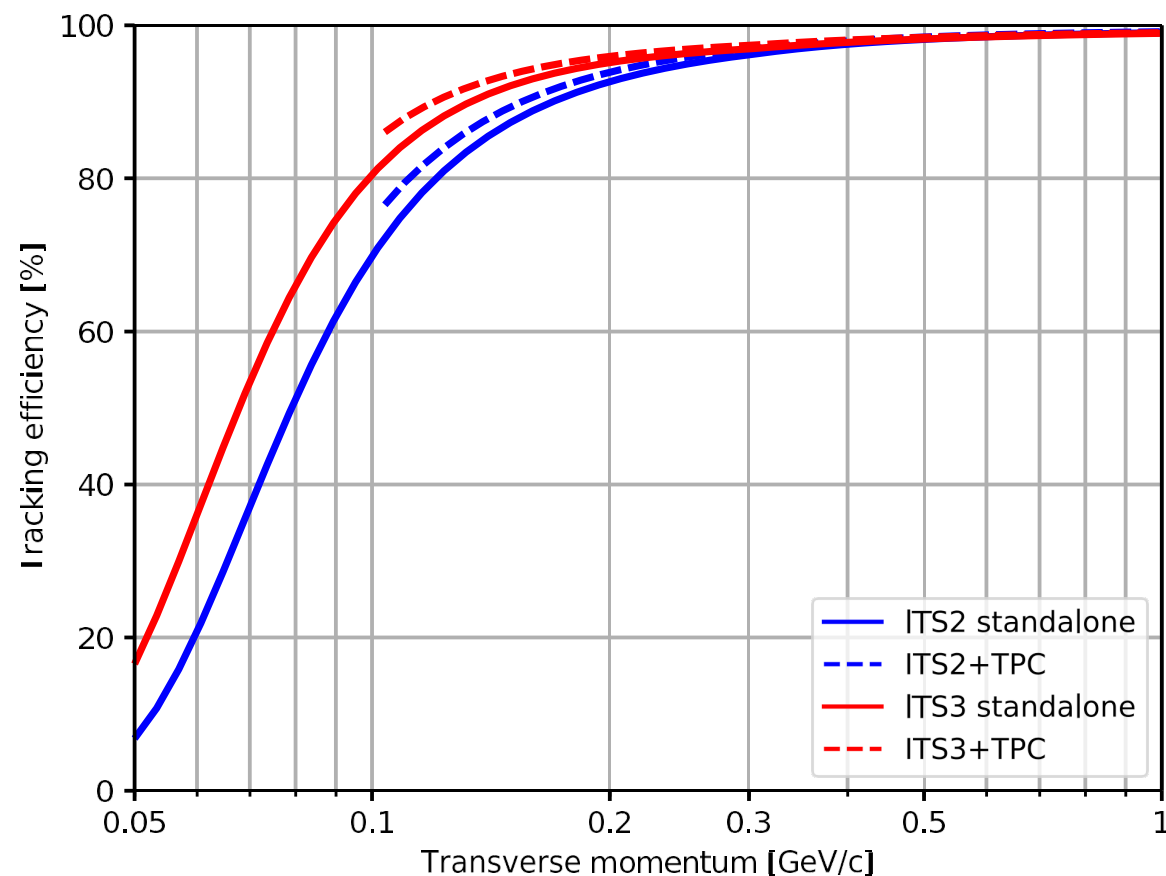
pointing resolution



[ALICE-PUBLIC-2018-013]

improvement of factor 2 over all momenta

tracking efficiency

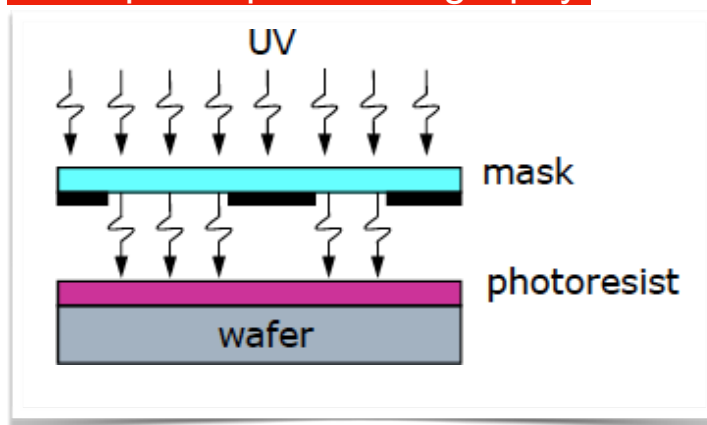


large improvement for low transverse momenta

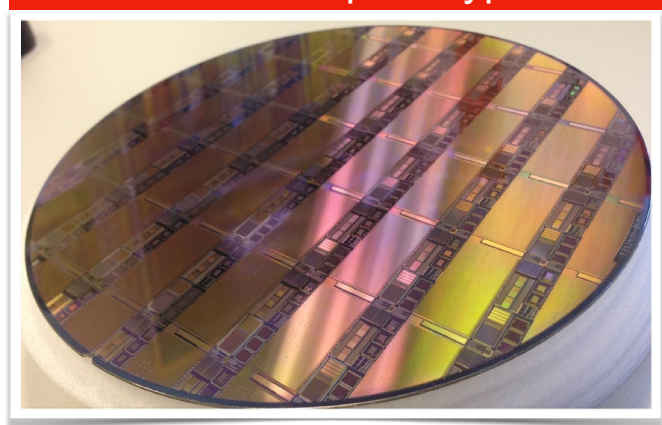
Wafer-scale chip in 65 nm CMOS process

- Switch to TowerJazz 65 nm CMOS process (ITS2/ALPIDE: TowerJazz 180 nm)
 - needed mainly because of larger wafers: $\varnothing=300$ mm (180 nm process only available on $\varnothing=200$ mm wafers)
- Stitching, i.e. producing chips as big as the wafer
- More details about the sensor development in the *next talk by Iain Sedgwick*

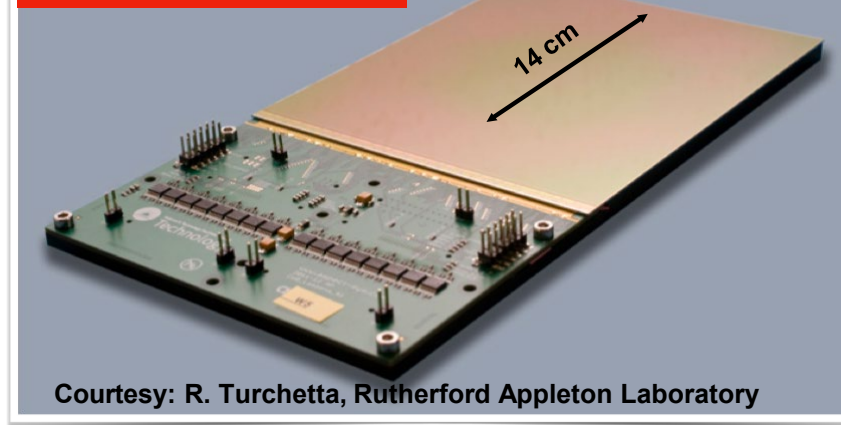
Principle of photolithography



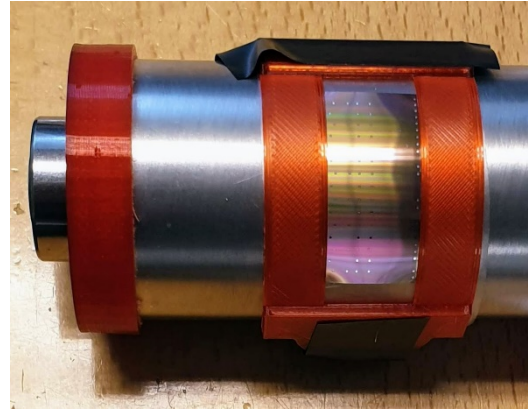
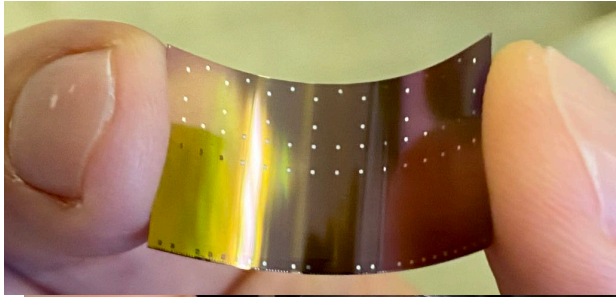
200 mm ALPIDE prototype wafer



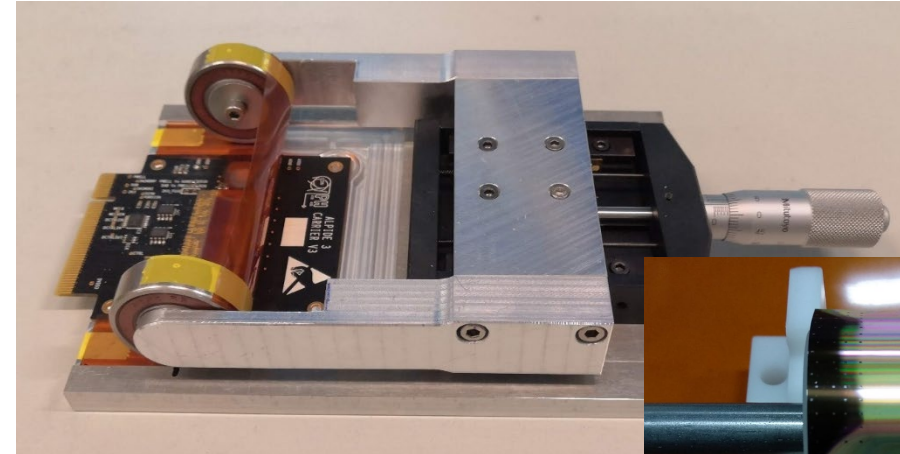
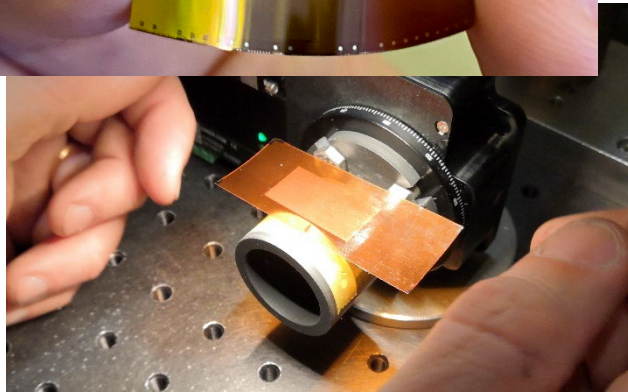
Wafer-scale sensor



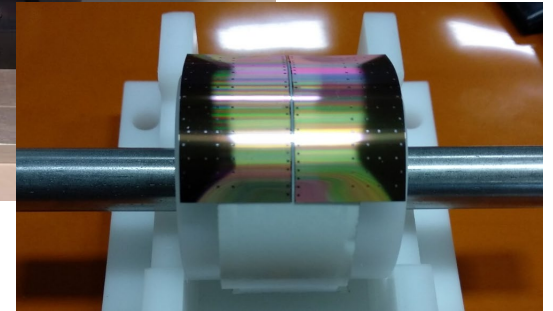
R&D on bending and thinning



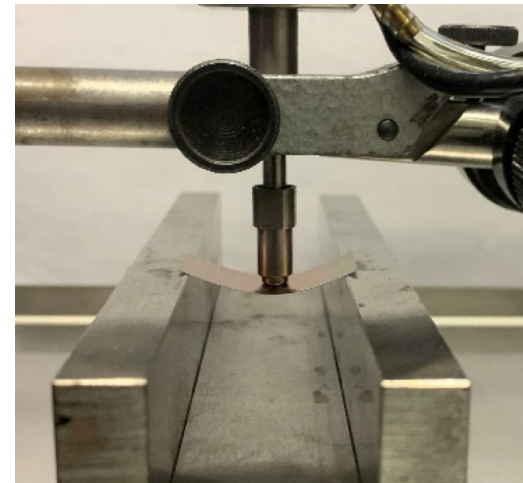
Manual bending



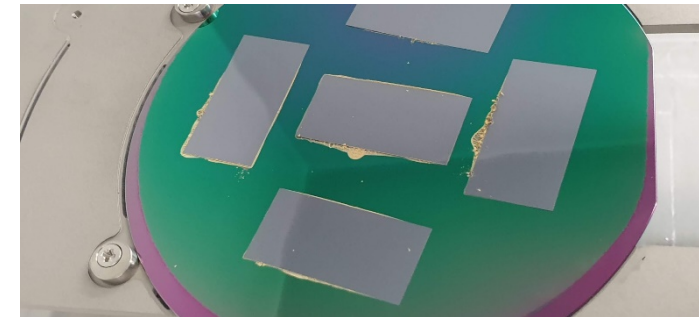
Controlled bending



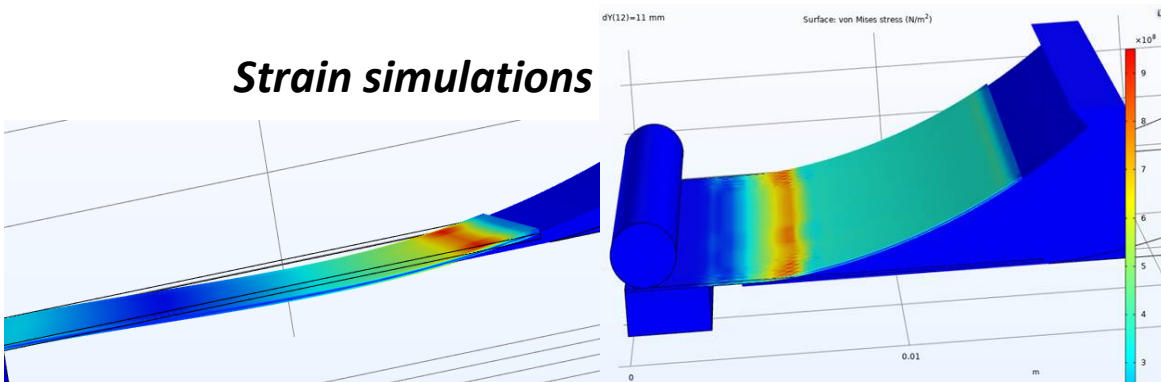
Bending tests



DRIE thinning tests



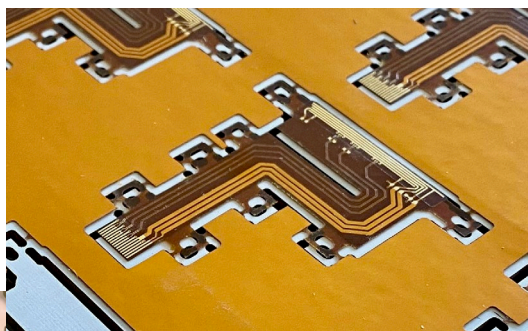
Strain simulations



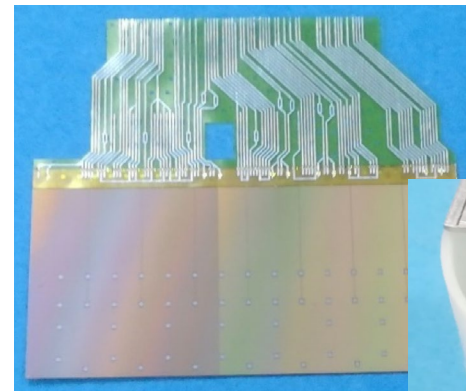
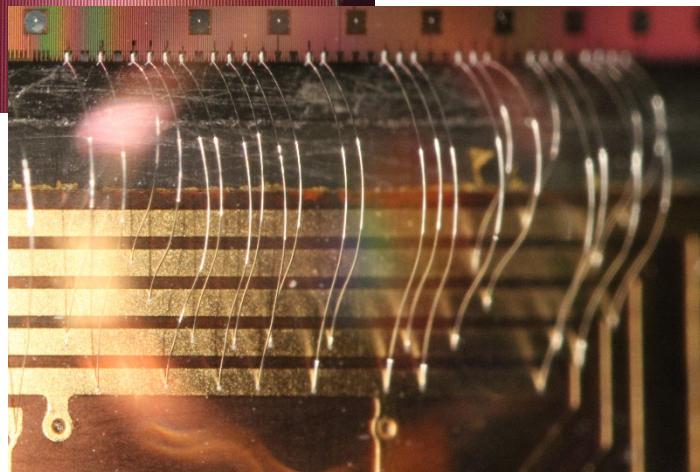
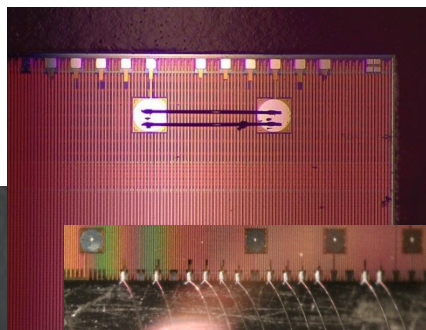
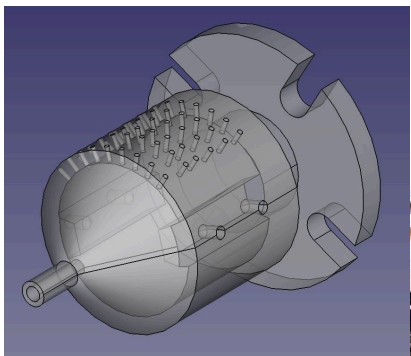
Tools and procedures for interconnections

- Several support tools and flexible circuits

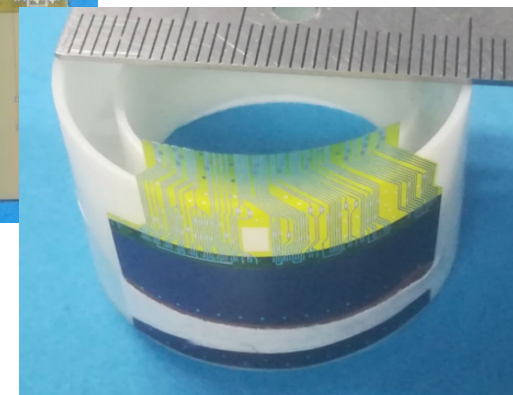
Bendable FPC



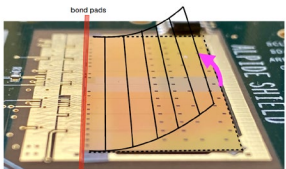
Cylindrical bonding tool



SpTAB bonding
Bending after bonding

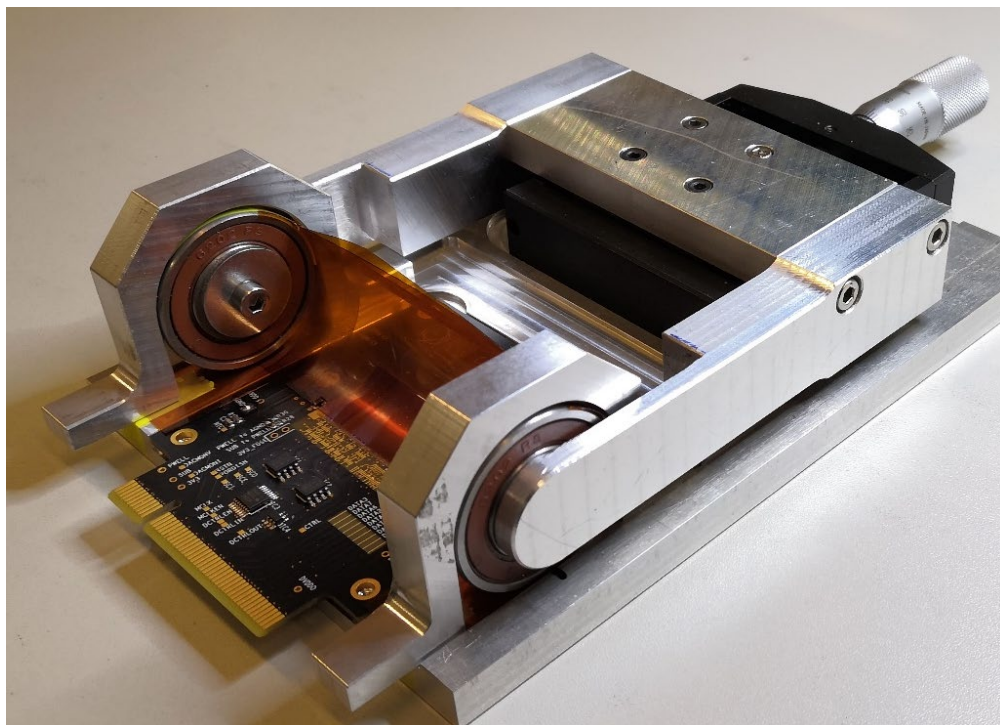
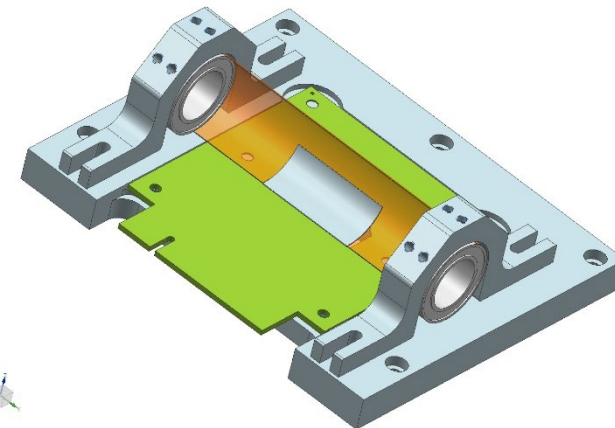
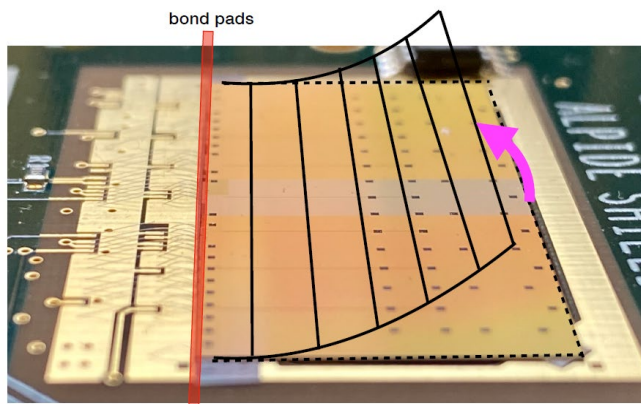


Wire bonding on curved surface
Bonding after bending

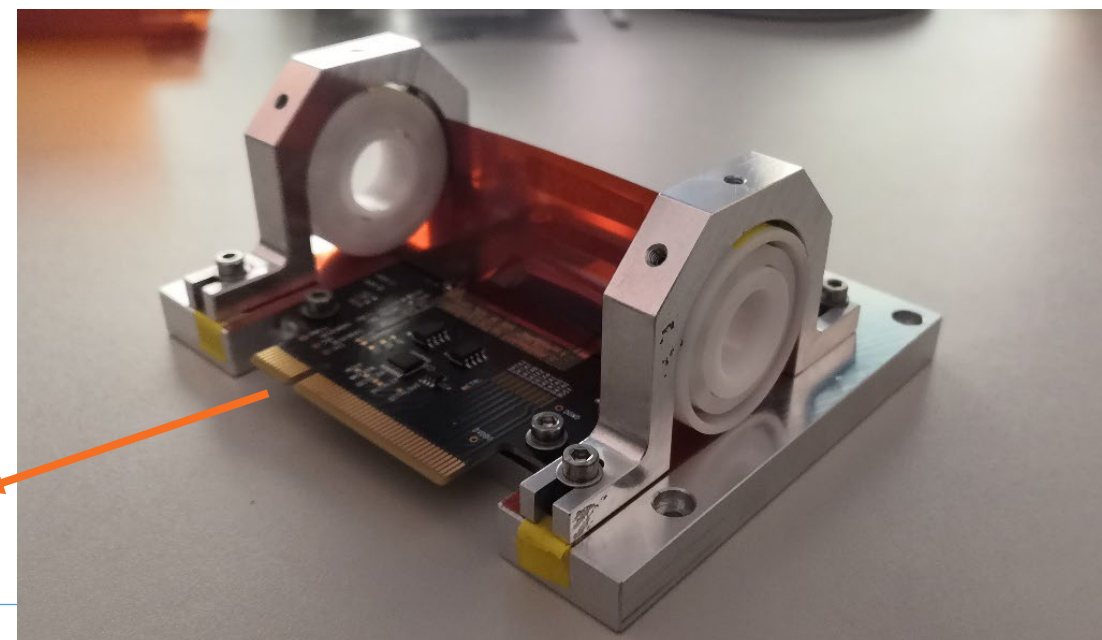


Bent 50 μm ALPIDE testing - 1

- **Bent along the short side**
 - Bending affects pixel matrix only
 - Bonding area is glued: flat and secured
 - Variable curvature (down to 1 cm radius)

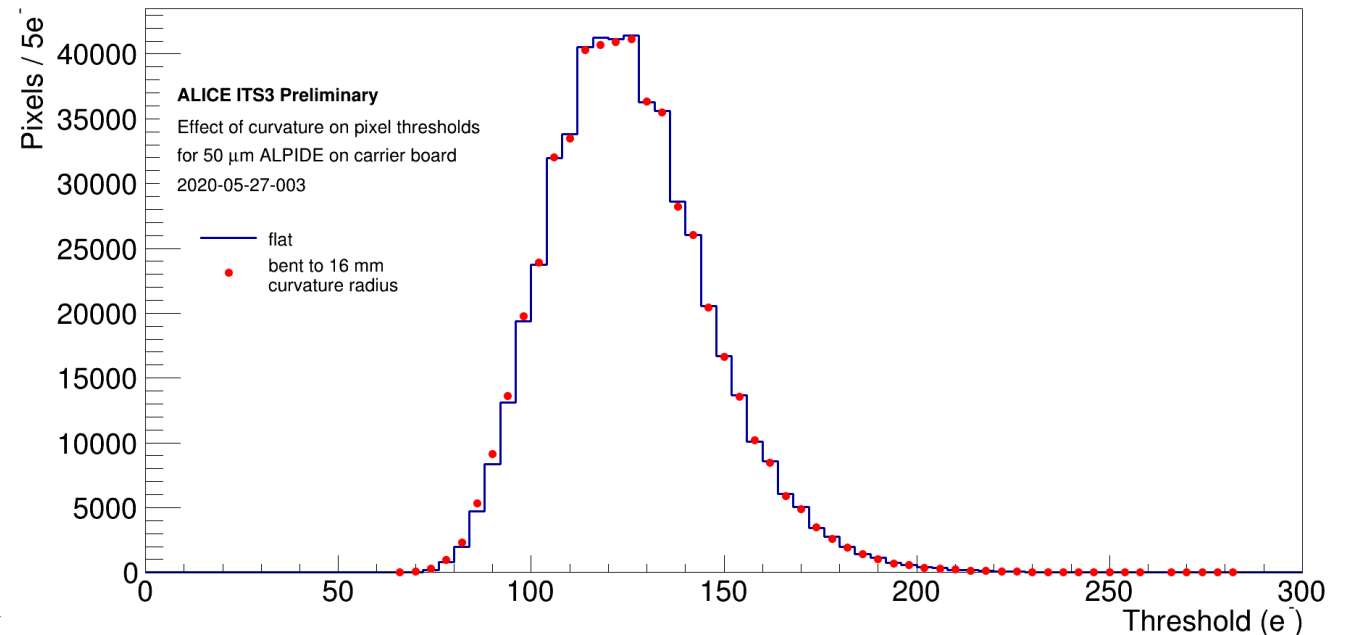


Single
chip
DAQ
board

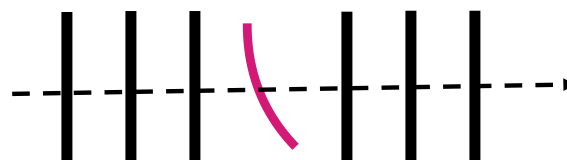
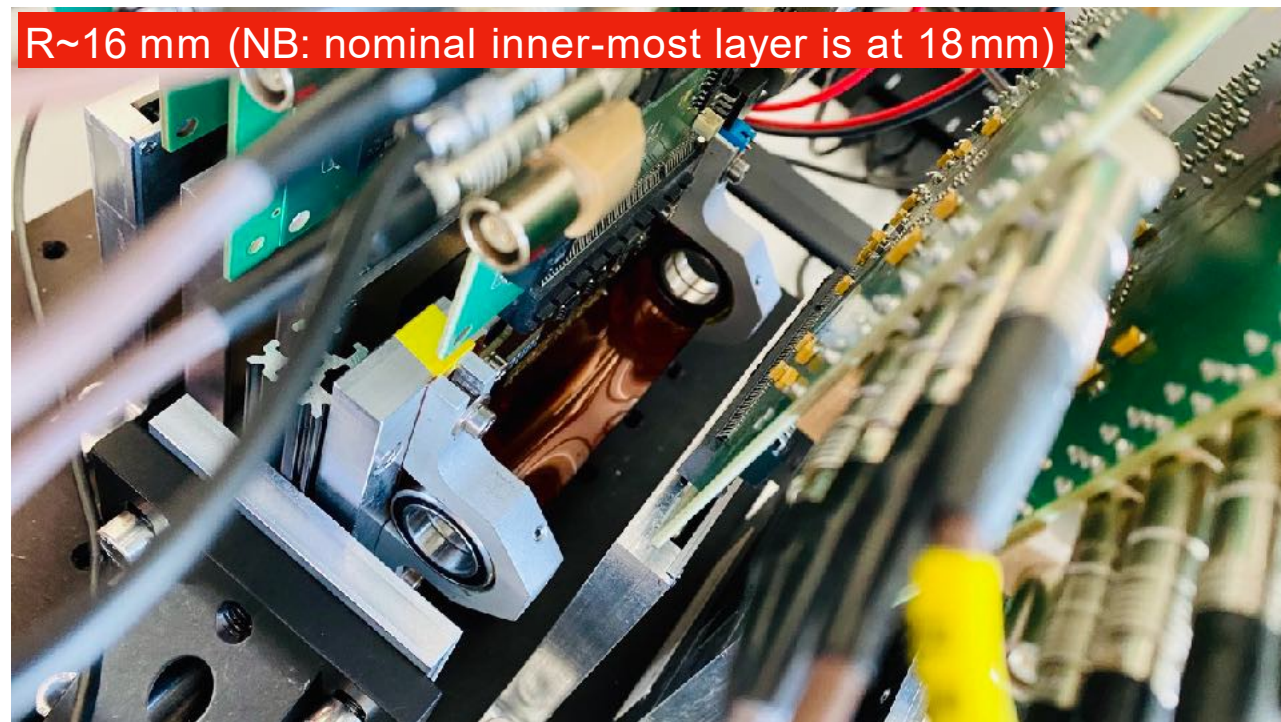
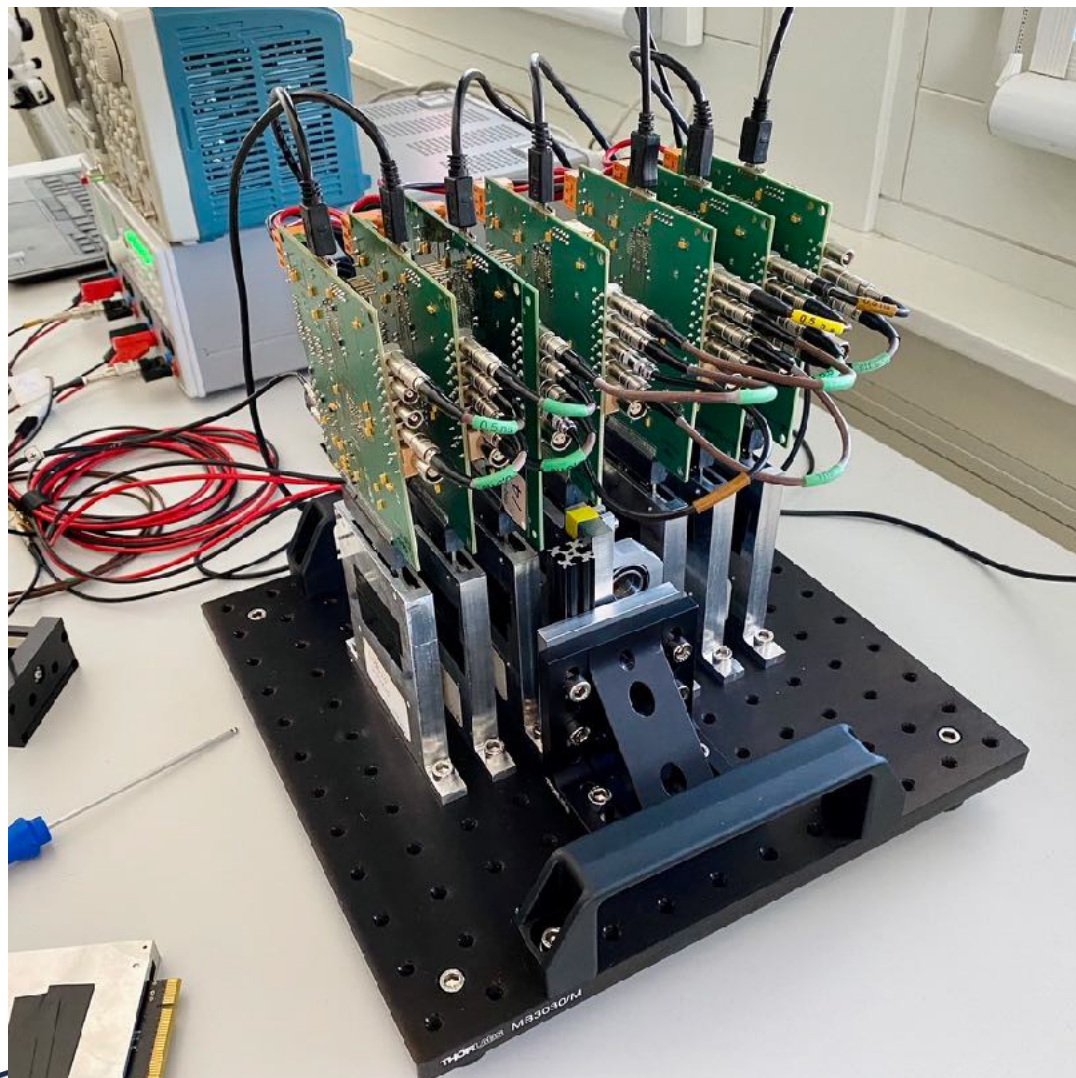


Bent chip electrical tests

- Laboratory tests to characterize bent ALPIDEs in terms of thresholds and fake-hit rate
 - different set-ups are tried
 - experience on handling is gained
- The curvature effect is not noticeable on:
 - pixel thresholds, FHR, pixel responsiveness
 - tested down to below nominal bending radius
- 3 chips successfully installed and tested in lab, 2 of them sent to DESY for testbeam



Bent chip in ALPIDE-based beam telescope

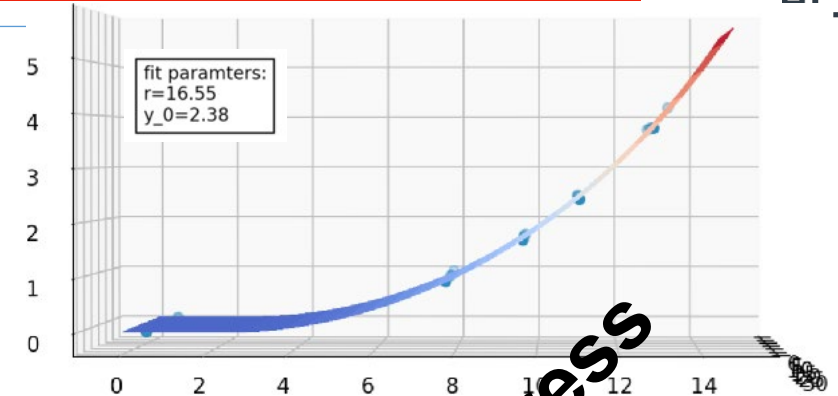


+ 2nd chip at R~18 mm

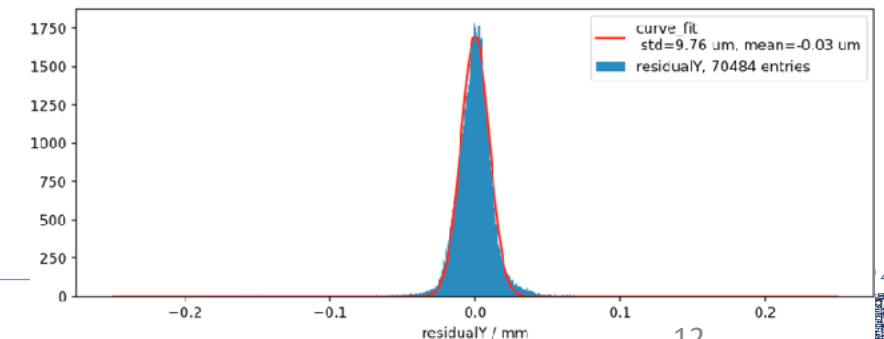
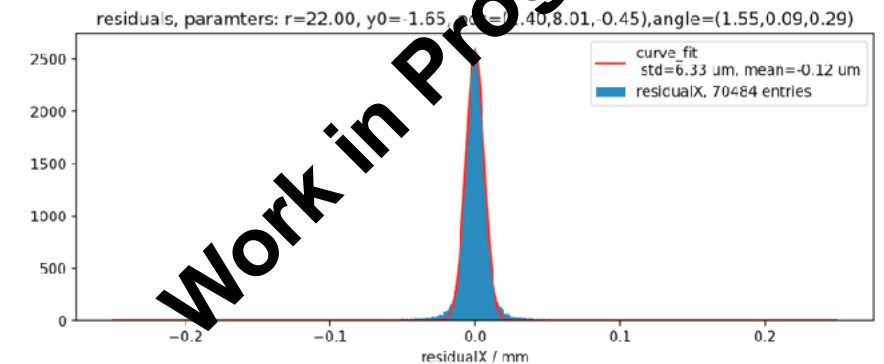
Testbeam data analysis ongoing

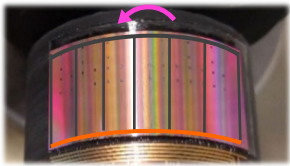
- Bent chip shape approximated as a purely cylindrical segment
- First look at the efficiency shows $>99.9\%$ at nominal 100 e^- threshold
- Main challenges:
 - Describe the surface with μm -precision
 - Hold the chip at the desired curvature:
 - measurements before and after the test show a curvature relaxation from 16 to 24 mm
 - least squares optimization of the cylindrical model yielded the DUT radius of 22 mm
- First paper in preparation

Coordinate measurement machine



Test beam data

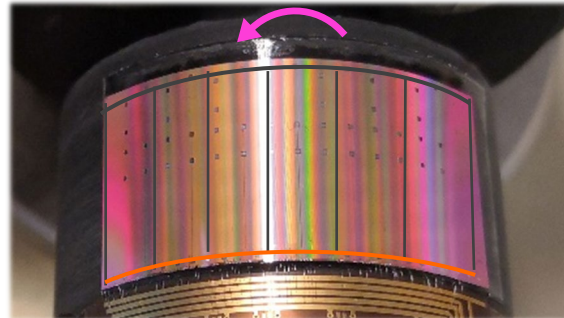




Bent 50 μm ALPIDE testing - 2

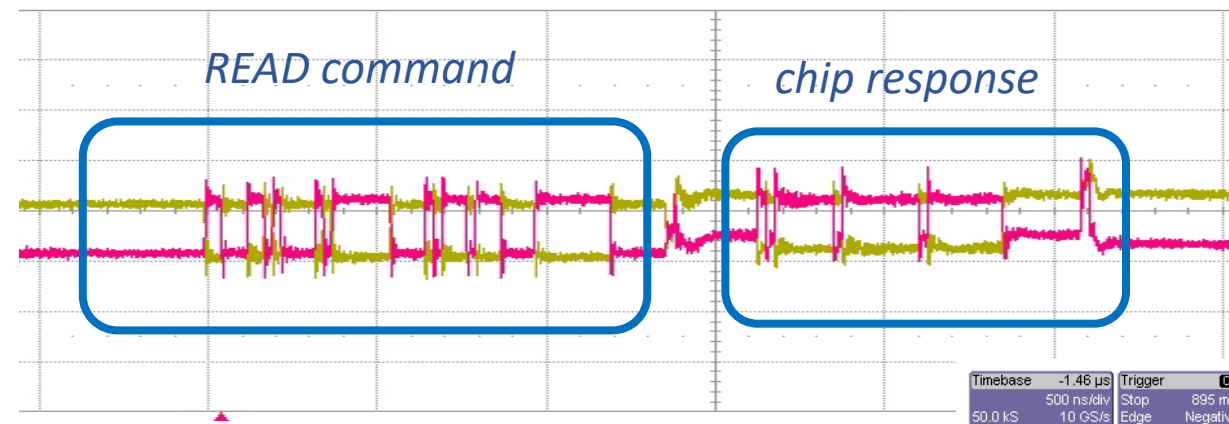
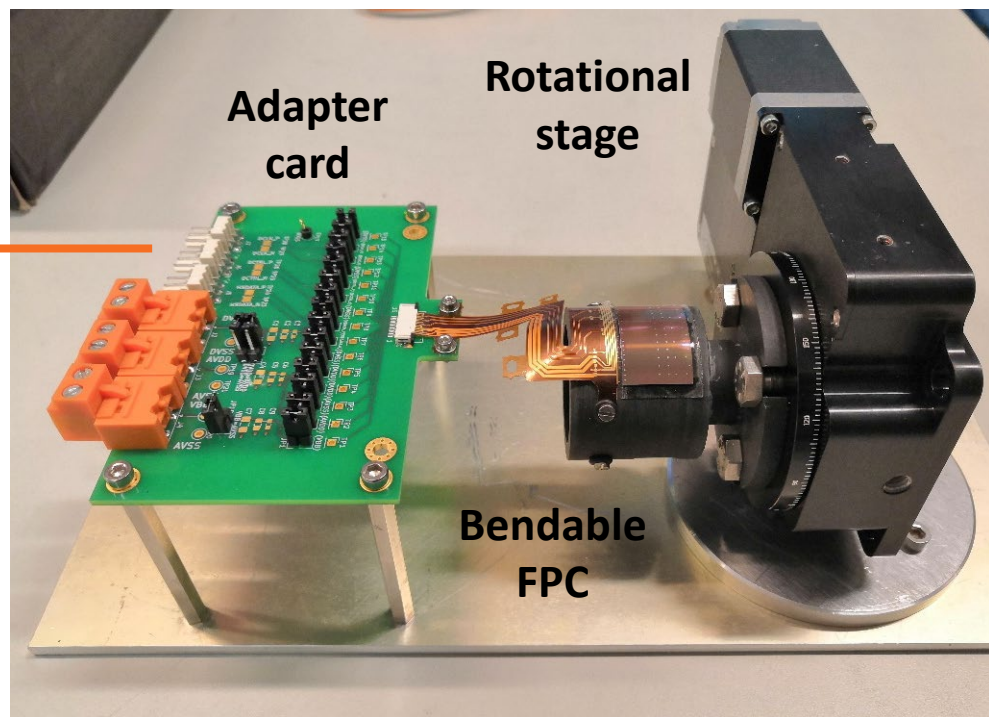
- **Bent along the long side**

- Affecting matrix and periphery
- Stretches the CMOS circuitry
- Completely glued onto support
- Fixed curvature (1.8 cm radius)

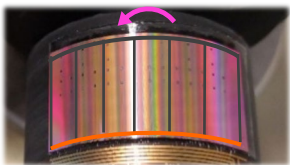


- Custom developed setup to interconnect the curved chip after bending
- I-V and response immediately checked after interconnecting the chip: works

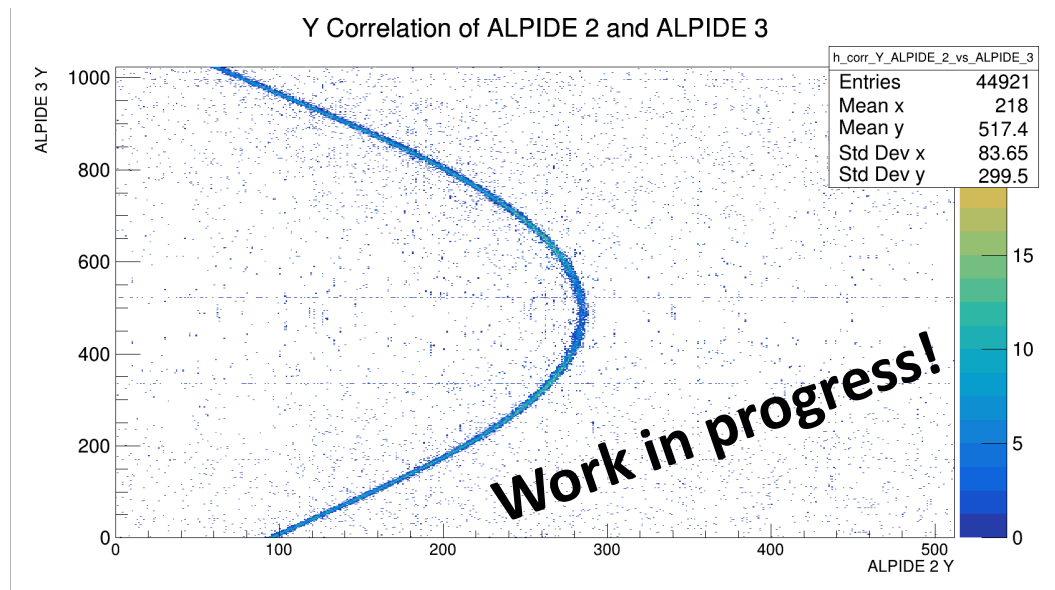
DAQ board /
Power Supply



- 5 chips successfully bent and tested.
- Handling tools to be improved to avoid accidents

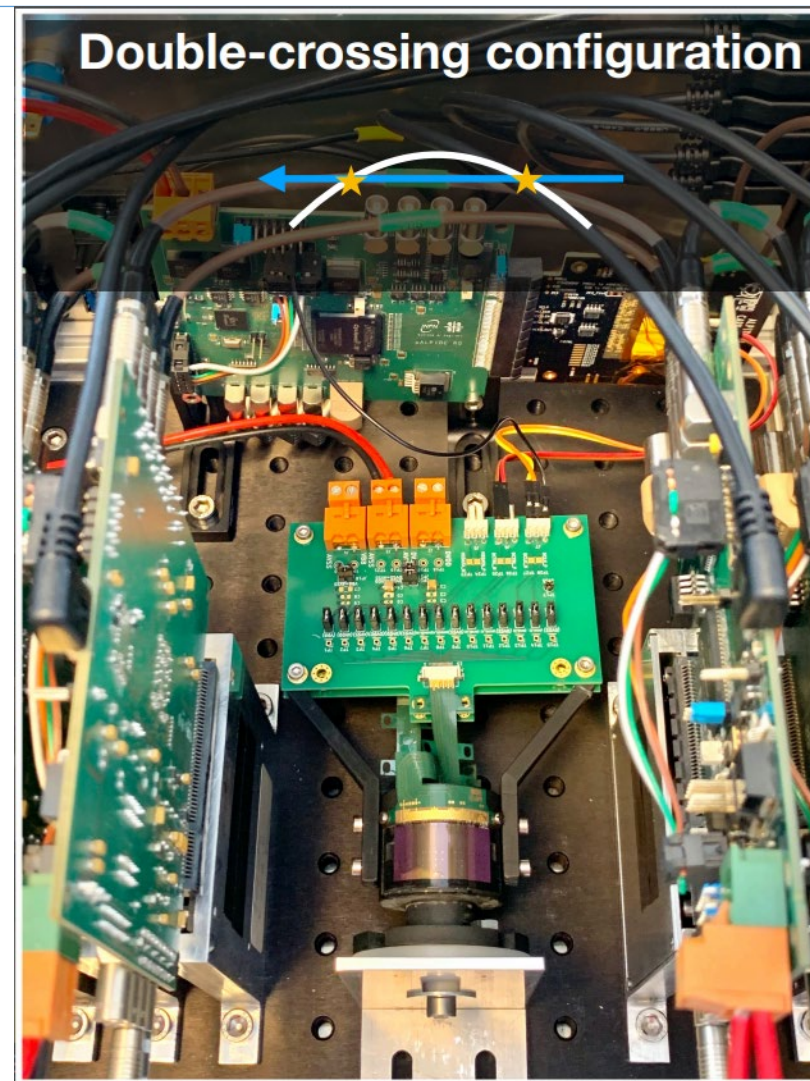


Testbeam happened last week



*Online monitoring
Correlation bent chip – reference plane*

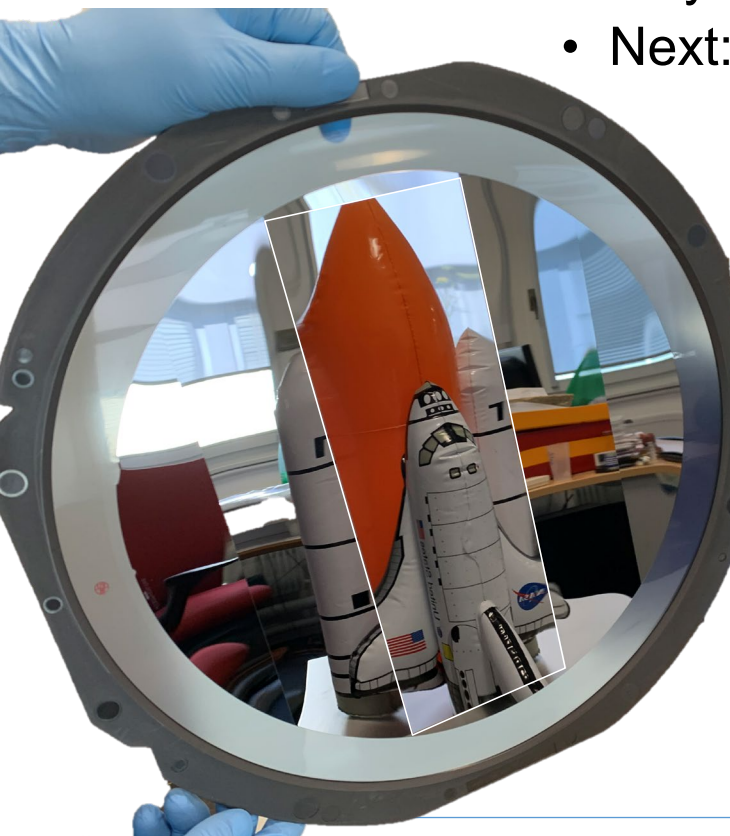
*Analysis is ongoing...
but the bent chip works!*



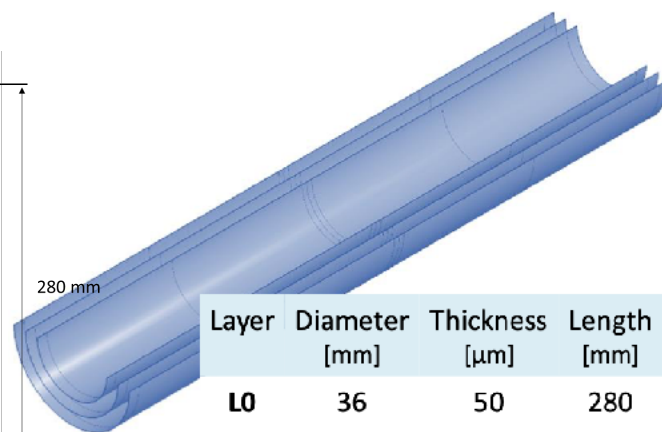
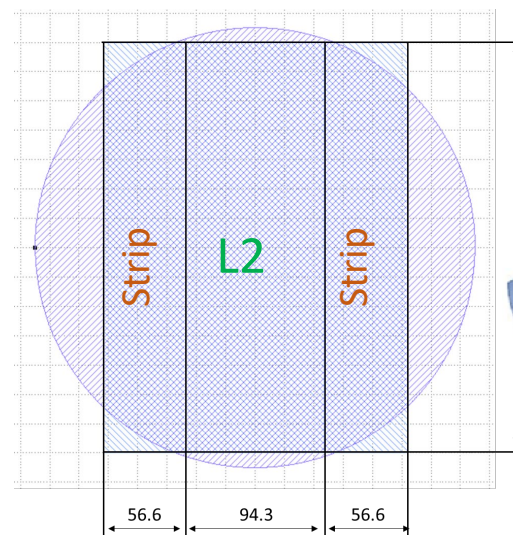
Towards the engineering module

Dummy chips: blank, 300 mm wafers were procured and thinned down to 50 μm , under test

- they will serve first integration steps
- Next: adding a metallization layer with a heater for thermal tests



12 inch wafer
D=300mm (11.8 inch)
<100> P-type
Initial th. = 775 μm



Layer	Diameter [mm]	Thickness [μm]	Length [mm]	Semi-circ. [mm]
L0	36	50	280	~56.55
L1	48	50	280	~75.4
L2	60	50	280	~94.25

Carbon foam spacer development



Company	Foam Name	Material Ordered	T. value (CHF)	
ERG	Duocel®	3 sets of rings + 1 sample	2087	10.06.2020
ALLCOMP	K9 Hi-K	1 set of rings + 1 sample for 2 different density (0.20-0.26 and 0.45-0.68)	5360	26.06.2020
CFOAM	35HTC	3 sets of rings + 1 sample	1500	17.06.2020
ENTEGRIS	POCO HTC	3 sets of rings + 1 sample	2735	TBD

► First spacers were machined

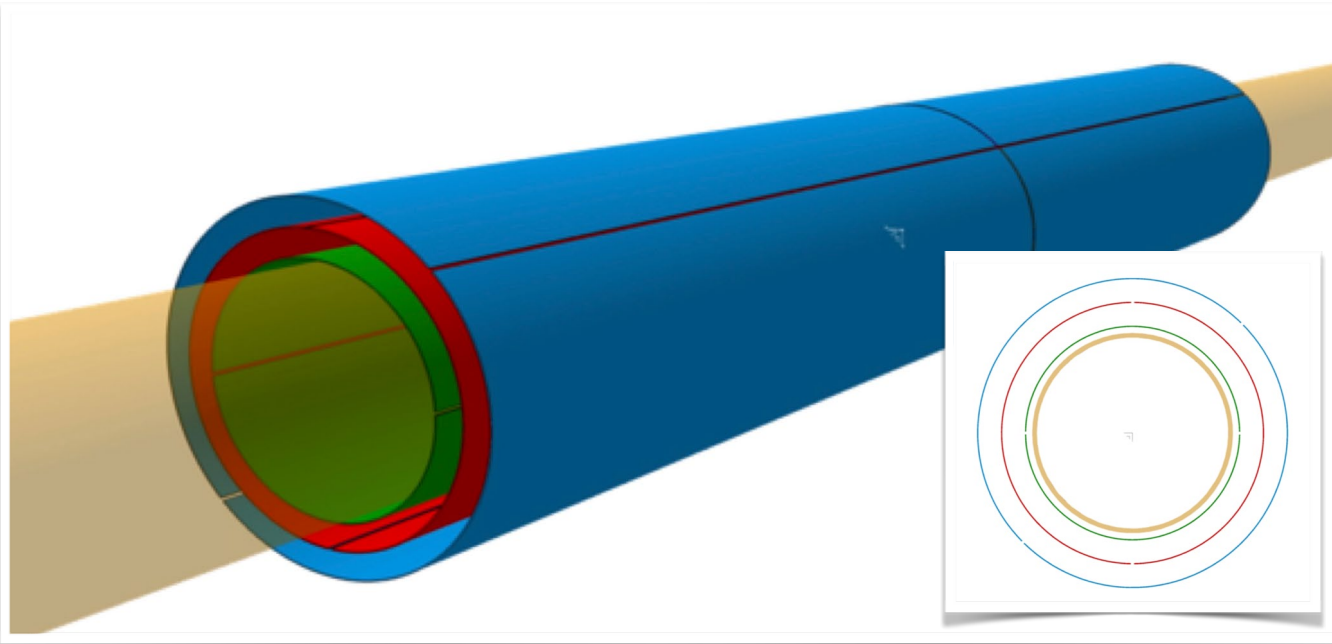


Conclusions

- The ITS3 Project has been endorsed by LHCC and has a fully operational organization
- R&D activities on the most challenging R&D topics are progressing well, and are generating interest beyond the ALICE community
- A new sensor based on 65 nm CMOS process is being developed (*see next talk*)
- Existing 50 μm thick ALPIDEs have been bent and tested, demonstrating that an ITS3 based on bent silicon is possible

Thank you for your attention!

Layout



- ▶ New beam pipe:
 - “old” radius/thickness: 18.2/0.8 mm
 - new radius/thickness: 16.0/0.5 mm
- ▶ Extremely low material budget:
 - Beam pipe thickness: 500 μm (0.14% X_0)
 - Sensor thickness: 20-40 μm (0.02-0.04% X_0)
- ▶ Material homogeneously distributed:
 - essentially zero systematic error from material distribution

Beam pipe Inner/Outer Radius (mm)	16.0/16.5		
IB Layer Parameters	Layer 0	Layer 1	Layer 2
Radial position (mm)	18.0	24.0	30.0
Length (sensitive area) (mm)	300		
Pseudo-rapidity coverage	± 2.5	± 2.3	± 2.0
Active area (cm^2)	610	816	1016
Pixel sensor dimensions (mm^2)	280 x 56.5	280 x 75.5	280 x 94
Number of sensors per layer	2		
Pixel size (μm^2)	O (10 x 10)		